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Update on Parts SEE Susceptibility from Heavy Ions

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PREFACE

Special thanks are due to Jim Coss, SEE group leader; Charles Barnes; John Zoutendyk; Peter Wang; Mike Havener; and Mike O'Connor, of JPL.

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INTRODUCTION

An ongoing single event (SEE) test program at JPL and The Aerospace Corporation continues, not only to assess specific part performance for interplanetary and satellite environments, but also to establish trends in SEE response of an ever-increasing body of device data.

In 1985, Nichols et al. [1] published the first nearly comprehensive listing of SEE test data for 186 parts. This presentation was updated in 1987 with the publication [2] of data for 83 additional parts and again in 1989 [3] with data for 154 more parts. In this report, the authors extend the data base for 182 new parts. As before, the data are collected according to technology, function, and manufacturer in order to identify trends, generalizations, and data gaps.

TESTING APPROACHES

The experimental procedures used by JPL and The Aerospace Corporation are evolutionary and are described in detail in previous reports [4,5]. In general, the procedures comply with the guidelines for SEE testing set forth by the ASTM F1.11 document [6].

ORGANIZATION AND SCOPE OF DATA

This report summarizes soft-error and latchup experimental test data from JPL; The Aerospace Corporation; the Applied Physics Laboratory, Johns Hopkins University (JH); Centre National D'Etudes Spatiales (CNES, France); European Space Agency (ESA); and other SEE testers. These data were provided directly to JPL or were otherwise made available to the scientific community during the two-year period from January, 1989, through December, 1990. The authors will include smaller SEE data sets generated by all U.S. and foreign researchers when these data are made directly available. Not included are proprietary data generated by subcontractors who used JPL hardware. Also omitted are now fairly extensive data sets on power MOSFET failures obtained by JPL, Rockwell International, Boeing, and others—such data require a significantly more complicated organization.

The SEE data presented here and in the previous three reports [1-3] represent a substantial majority of all test data obtained on SEE throughout the world. Some of the remaining data may be found in previous issues of *IEEE Transactions on Nuclear Science*, other journals, or in published and unpublished presentations of SEE symposia.

The data from all organizations are summarized and collected together, even though there are minor differences in the data from each organization. For example, JPL defines the threshold linear energy transfer (LET) as that value of LET where soft errors are first counted at fluences of 10^6 ions/cm²; The Aerospace Corporation currently defines their LET threshold as that point where the measured upset cross section is one percent of the measured maximum cross section. These two values may be quite different.* To obtain accurate single event upset (SEU) rates for a

^{*} The use of an LET threshold defined as a stated percentage of a maximum (saturated) cross section attempts to establish a practical lower bound for the purpose of estimating upset rates. The discrepancy between this definition and JPL's definition becomes academic when a complete cross section is used in rate calculations.

prescribed radiation environment, one requires the entire plot of cross section versus LET, which may be available from the parent test organization.** More recent JPL data may be accessed directly from JPL's computer data base, RADATA.

All data are conveniently divided into two tables: Table 1, for MOS devices, and Table 2, for a shorter list of recently tested bipolar devices. In addition, a new table of data for "Latchup Tests Only" (invariably CMOS processes) are given in Table 3. Those devices having both softerror and latchup data are reported in Table 1. All data listed here represent a substantial abbreviation and ignore statistical features altogether. SEE tests use a dynamic nominal bias; latchup tests are usually performed at the maximum value of the nominal bias range—a condition that usually (but not always) enhances the possibility of latchup. Unreported transients and higher test temperature measurements may exist for some parts. Therefore, a system designer interested in a specific part is urged to contact the appropriate test organization for further information.

Users are cautioned that manufacturers (listed with their abbreviations in the Appendix) may often change their process (and resultant SEE susceptibility) without changing the part number or notifying tester organizations. Thus, a test of flight parts is always a good policy.

TRENDS

Some trends in the recent data are offered in the "Remarks" column, but for the most part the table speaks for itself. Special studies (such as SEE response variation with temperature, or latchup susceptibility versus epi-layer thickness) are beyond the scope of this presentation.

^{**} More detailed data are available in JPL Publication No. 88-17 by D. K. Nichols et al., "Heavy Ion Induced Single Event Phenomena (SEP) Data for Semiconductor Devices from Engineering Testing" (July, 1988). This report includes cross sections and identification of ions and beam angles.

CONCLUSIONS

The new data presented here can be combined with data given in References [1-3] to develop certain generalizations useful for protecting flight electronics from SEE. Hard technologies and unacceptably soft technologies can be flagged. In some instances, specific tested parts can be taken as candidates for key functions—such as microprocessing or memory. As always with radiation test data, specific test data for qualified flight parts are recommended for critical applications. Calculations of accurate SEE rates will require the assistance of a computer code, a well-defined environment (in terms of flux versus LET), and a complete device characterization (cross section versus LET, at the appropriate temperature). Evaluation of catastrophic effects requires its own statistics in which flares are considered. JPL's recent concerns with power transistor burnout and single-event gate rupture are beyond the scope of this report. The Aerospace Corporation's exploration of SEE transients in linear devices may later open up a whole new concern for a device category formerly considered to be no problem.

1989-1990 (MOS AND NMOS DEVICES)

	'89. Same results n interface adapter.	erospace at 88-in.	4S-37, 1. ('88)	d 11/89. Current	ET = 75.	ıre hard. Feb. '89	Feb'89		eb. '89.	io. s section.		> 6€
Remarks	With Aerospace at 88-in. Feb '89. Same results with IPN Tandem. Device is an interface adapter.	No latchup at LET = 40 with Aerospace at 88-in.	See F.W. Sexton et al, IEEE NS-37, p1861 (Dec. '90). Compare JPL ('88)	Similar to NS32201, 10/88 and 11/89, Current surges, Ambient T = 85C	JPL: Mask No. 3227, Feb. '89 JH: DC 8817. No latchup at LET = 75.	Mask 3582; half of elements are hard. Feb. '89	No latchup at 125 degrees C. Feb'89 Programmable Interval Timer	Latchup at LET = 60. Feb, '89 Thick epi permits latchupl	No latchup at T=70 deg. C. Feb. '89. Clock Generator.	F9450-compatible, Chapuis '90, LU and SEU have same cross section.	LU LET > 100. May '90.	1750-compatible. Test 504 MeV Xe @ 70 degree angle. May '89
Facility	88-in & IPN	88-in	BNL	BNL & 88-in	88-in	88-in	88-in	88-in	88-in	N	88-in	88-in
Cross Section Per Bit (sq mlc)	ı	100	re size) Ire size)	1	ı	١.	l	I	ı	I	1	No Upset
Device Cross Section (cm2)***	2E-3	2E-3	35 (2 micron feature size) 23 (1.75/1.25 feature size)	I	I	1/2 of above cross section	ı	4E-4	1	Partial	5E-4	No upset
Effective LET** Threshold	Ω.	₆	35 (2 23 (1	40	က	က	52	0	52	5±1	50	180
Bits Effe LE Thre	48 tested	128x8 RAM	I		i	I	96	160	3 out of 49	ı	I	~200 tested
Mfr.†	THO	MTA	SNL	SNL	HAR	HAR	HAR	HAR	HAR	PFS	ALS	MED
Function Technology I	NMOS	CMOS/EPI	CMOS/bulk No resistor	ароле	CMOS/epi	CMOS/epi	CMOS	CMOS/epi (12-micron)	CMOS	CMOS/EPI	CMOS/epi	CMOS/SOS
function 1	Peripheral to 6800 microproc.	MicroP	MicroP (16-bit)	Peripheral to SA3300	MicroP (16-bit)	MicroP (16-bit)	Peripheral to 80C86	Peripheral to 80C86	Peripheral to 80C86	MicroP (16-bit)	MicroP (16-bit)	MicroP (16-bit)
	EF6821CM	80C31L	SA3300	SA3304	80C86RH	80C86RRH	HS82C54RH	MD82C54	НЅ82С85ВН	P1750A	BX1750A	MAS281
Test Org* Device	CNES	CNES	SNL	7	HC/C	7	7	CNES	~	CNES	∢	7

"J = JPL, A = Aerospace Corp., R = Rockwell Int. or IRT (J. Pickel), SNL = Sandia, NTT = Nippon Tel & Tel Corp., IBM = IBM, H = Hughes (El Segundo, CA), LIN = .incoln Labs, M.I.T., CNES = Centre National d'Eudes Spatiales (France), GD = General Dynamics (J. Elliott at SEE Symposium, April, '90), ESA = European Space Agency
JH = John Hopkins Applied Physics Lab.
"**LET is Linear Energy Transfer = the density of ionization along an ion's path in MeV/(mg/cm²).
"**LET is Linear Energy Transfer = the density of ionization along an ion's path in MeV/(mg/cm²).
"**Cliness only at a cross section (upsets/fluence per device) is given for 120-360 MeV krypton (or bromine) at normal incidence, having an LET = 37-40
MeV/(mg/cm²).
MeV/

TABLE 1 SEU DATA (CONT'D) 1989-1990 (MOS AND NMOS DEVICES)

Remarks	No latchup. No SEUs from alphas and protons.	Latchup cross section = 1E-5 cm ² .	5-micron epi.	Test of 5 developmental parts with varying epi thickness & n-well dimensions. B.H. Maurer (8/90).	LU LET = 12; 1E-3 cm ² , Feb. '90. LU(th)=8. Aug 90. V. Slerrino-LIN	LU LET = 8; 1E-4 cm ² . May '90.	High temp data available, 10/87; 6/86; 2/89.	No latchup, 1.5 micron technology, Feb. '90	Latchup (S. Mattsson, Saab Space) Compare eartler Aerospace 6/87 and below.	LU(th) = 6 LU cross section = 5E-4 cm ² . IEEE (NS '90). See above	A: Latchup at LET - 15, 12/87, JH; Agrees 8/90.	LU<40 with 1E-3 cm ² , Feb. '89,	LU = 22 with 3E-3 cm ² . July '89.	LU- 11 with 8E-3 cm ² . Sep. '89.	LU(th) <26. Aug 90. Sterrino-LIN	No latchun, Feb'90, Compare below.	LU LET-15 with 1E-5 cm ² , A: 1/89.	Multiple soft errors per ion. LIN: 8/90	LU LET = 15; >2E-3 cm ² . Mar. '90,	Latchup at LET <<12. Fab. '90.	No fatchup. May '90.	LU LET - 25, 6E-5 cm ² . Nov. '89.	LU LET(th) <13; LU cross section = 3E-4 cm2.	TATOUR-SOCIETISE DEC. 80.	Harboe-Sorensen Dec. '90.	NoLU >54. 8/90. Sterrino-LIN	No latchup, 8/90, Compare to IDT71256 listed above.	Latchup at LET = 80. J: Mar. '90. A: May '90.	LU(th)s26; 6E-6 cm ² , Aug 90.	1U LET = 25: 4E-4 cm ² . May '90.	LU LET = 55: 2E-5 cm ² . Fab. '90	LU LET = 85 1E-6 cm ² . May '90.
Facility	Cf-252	Previous	CI-252	BNL	88-in BNL	88-in	_		CI-252	Van deG	88-In	88-ju	88-In	98-in	BNL	N N	88-in	& BNL	88-In	N N	88-In	88-in	Ndi	701	*	BNL	BNL	88-in	BNL	88-in	88-In	88-In
Cross Section Per Bit (sq mic)	~100	~100	80	I	11	1	60	No upset	i	1	1	1	I	i	i	1	I		l	1	ı	i	200	450	2	i	40	9	l	ſ	1	ı
Device Cross Section (cm2)***	 1	ı	ì	1	11	2E-4	4E-4	No upset	1	1	0.2	0.1	5E-2	2E-2	Į	~0.5	~0. 6		>0.2	0.5	4.0	-	1	-	İ	3E-2	0.1	9.0	í	0.1	8.0	9.0
Effective LET** Threshold	9	9	i	13	۱ %	-	15	×72	I	ı	2.5	m	.	ro	4.1 ×	<1.7	4.1 ^		V.	1.7	က	Ç	S)	ų	י	<1.4	4	4	5,	O	ന	*
Bits E	00-	100	i	1	Memory	16X4	16K×1	16K×1	64K×1	64Kx1	32Kx8	32Kx8	32Kx8	16K×4	2Kx8	32Kx8	32Kx8		64K×1		32Kx8	32Kx8	2Kx8	07/0		32Kx8	32Kx8	128Kx8	32Kx8	32Kx8	128Kx8	128KX8
Mir.†	IN	Ν̈́	IN T	ADI	ADI MOT	CγP	HCA	MED	TOI	IOT	TQ1	SE	N N	PFS	S	S	S		Z	Σ Z	NEC	₹	Ħ	HIT	•	둗	Ħ	높	SNY	SNY	SNY	NEC
Technology	CMOS/epl	CHMOS IV	CHMOS IV	CMOS/epi	CMOS	CMOS	CMOS/SOS	CMOS/SOS	NMOS/CMOS	NMOS/CMOS	NMOS/CMOS	CMOS	CMOS	CMOS	1	i	CMOS/NMOS		NMOS	i	NMOS/CMOS	CMOS	NMOS/CMOS?	j	ľ	1	ı	NMOS/CMOS	ſ	CMOS	NMOS/CMOS	CMOS
Function	MicroP	MicroP	(32-bil) MicroP	(32-5/1) Digital Signal	DSP DSP	SRAM		SHAM	SHAM	SHAM	SHAM	MARK	SPAM	SHAM	SPAM	SHAM	SHAM		SHAM	SRAM	SHAM	SHAM	SHAM	CDAM		SRAM	SHAM	SHAM	SRAM	SHAM	SRAM	
Device	80386	80386	90386	ADSP2100A D	ADSP2100A 56001	CY7C189-15DC	CMM6167	MA9167	IDT7187	DT7187	IDT71256	SACKXB	OW5962	P4C1881	MT5C1608	M2568C	MT5C2568		IMS1600SL	IN1630SL	UPD43256	84256	HM6116	LIMESEA	10701	DPS92256	71256	HM628128	DPS92256	CXK58225	CXK581000P	MSM8128SLMB
Test Org*	IBM	IBM		Space JH	ر <u>۲</u> ۲		Α'n	CNES	Saab	Boeing	A/IH	•	(∢	<	Z	CNES	ALIN		<	CNES	<	<	ESA	V		Z Z	퐁	A/A	LIN		<	<

TABLE 1 SEU DATA (CONT'D) 1989-1990 (MOS AND NMOS DEVICES)

		~.·			resistor ept. '89.	m ² . Dec '90.	m ² , Dec '90.	h Cf-252 failed 52 ions.									table.								
Remarks	Latchup at LET = 40, 10/90.	LU < 27; 1E-4 cm². Harboe-Sorensen 12/90	LU LE 1 (m) > 54. Chapuis 90.	No latchup. Dec. '89.	Extensive data available at high temps and resistor values, other than 500 ohms used here. Sept. 89.	LU LET(th) = 13; LU cross section = 1E-4 cm ² . Dec '90.	LU LET(th) < 15; LU cross section = 6E-4 cm ² , Dec '90,	Latchup with Kr. Feb. '89. An earlier test with CI-252 failed to indicate latchup due to low range of CI-252 lons.	No latchup with 212 MeV Br. Feb. '89.		No latchup at LET = 72. Feb 90.	Latchup LET ≈ 50. Date Code: 8930. See Chapius IEEE NS 12/90.	Cross section vs LET given by T. Bion, IEEE Trans. NS-36, p2283 (Dec 89).	R. Harboe-Sorensen et al, IEEE Trans Nuc. Sci. NS-37, p1938 (Dec 90).	See J. Zoutendyk, IFEE Trans NS-36, p 2267 (Dec. 89) and earlier data.	No LU >100. Sep '89.	Bradley et al, Latchup. See "Latchup Only" table.	No latchup. May '90.	No soft errors nor LU at LET<120.	No LU >54. Aug 90. Sferrino-LIN	Latchup LET <<37, See LU Table.	No LU >100. Sep '89.	LU=15 with 2E-3 cm2, Sept '89,	Output buffer upsets.	Address register upsets in all "0's" mode. No latchup at LET=120, Oct '90.
Facility	88-In	<u> </u>	Z	88-in	BNL	M	M	88-in	<u>N</u>	GANIL & IPN	M	GANIL 8 IPN	88-in.	<u>R</u>	BNL	88-in	CI-252	88-in	BNL	BNL	BNL	88-in	88-in	CI-252	88-in
Cross Section Per Bit (sq mic)	100	300	l	1	ł	200	80 80 80 80 80 80 80 80 80 80 80 80 80 8	120	I	l	300	300	300	200	1	1	I	I	1	i	1	I	l	N/N	N/A
Device Cross Section (cm ²)***	6E-2	1 5	4E-Z	2E-2	I	ì	3E 2	2E-2	i	1	5E-2	0.2	0.2	I		2E-3	3E-6	2 to 10E-4	I	١	1	5E-5	I	3E-6	2E-5
Effective LET** Threshold	6	က် '	٥	52	06 <	တ	4	9>>	1	I	က	2.5		φ	~	10	1	3 to 10	ı	1	1	12	5	l	19
83 83 83	16Kx4	2KXB	۲ <u>۵</u>	2Kx8	8K×8	4Kx1	2Kx8	2Kx8	2Kx8	16Kx1	16Kx1	8Kx8	64K	16Kx4	256K	32Kx8	32Kx8	32Kx8	32Kx8	32Kx8	32Kx8	8Kx8	8Kx8	2Kx8	2Kx8
Mfr.+	E,	S	2	NO P	HOH	HAR	HAR	HAR	MTA	MTA	MTA	MTA	TN	ξ	MIC	ATM	SEQ	SEO	SEO	SEO	X	ATM	CYP	HAR	HAR
Function Technology Mir.†	CXMOS/epi	SONO	SCOMOL	CMOS	CMOs/epi (4-mic epi)	CMOS	CMOS	CMOS/epi (12 microns)	CMOS/epi	CMOS/bulk	CMOS/epi	CMOS/epi (12 micron)	NMOS	NMOS	NMOS	CMOS	ı	CMOS/epi	CMOS	١	CMOS	CMOS	CMOS	CMOS/epi	CMOS/epi
Function	SRAM	SHAM	250	SHAM	SHAM	SHAM	SHAM	ŞRAM	SHAM	SHAM	SHAM	SRAM	DRAM	DRAM	DRAM	EEPROM	EEPROM	EEPROM	EEPROM	EEPROM	EEPROM	UVEPROM	UVEPROM	PROM	PROM
Test Org* Device	51098	100016	- CM-	HC6116KSH-T	HC6364	HM6504	HM6516	HM6516	HM65162	HM65262	HM65262	HMS65641	2164A	TMS4416	MT1259	28C256L	28C256	28C256-250	28C256	CJ28C256	28C256	27HC642	CY7C263	HM6617	HS-1-6617RH
Test Or	٦,	CNE	CINES.	∢	NOH	ESA	ESA	7	CNES	CNES	CNES	CNES	∢	ESA	ا د	⋖	СD	∢	퐁	Z	ᆨ	∢	⋖	G	7

TABLE 1 SEU DATA (CONT'D) 1989-1990 (MOS AND NMOS DEVICES)

	4/90	; ; ;		06, sjinor	puls '90.	, jc	1/01	. ×					99		.90.		ું જ	.06.	, co	ļ					
Remarks	A: LU LT = 25, 1E-2 cm2, Jan. 199. GD: Latchup @ 55° C = 1E-4 cm2, 4/90.	No LU>100. J≲n '89.	1.U LET >100. Mar '90.	LU LET(th)<13 Actes (amily Chapuls '90	LU LET(th)=12. Actel family, Chapuls '90.	No latchup. Feb '90' 10 micron ep	Same as previous. Compare to above .I.D. Kinnism 1/91	"Remarkably similar to above " I O K	LU=15 with 7E-4 cm ² . Dec '89	LU LET=15: 1E-1 cm2 May ' 90	LU(th) <26; 4E-6 cm ² , Aug 90	No latchup. May '90.	0000 O 0 400 000 001 111 AN	10 LU 2 120, Dec 69, Fall D.C. 68	Latenup, See Lu Uniy Table, Feb '90.	No 111 - 120 Air '80 Part DC 8922	No LU>120, Dec '89, Part DC 8922.	Latchup, See LU Only Table, Feb '90,	No LU>120, Dec '89, Part DC 8948.	No LU >100, Feb '89.	No latchup. Mar '90.	No latchup. Mar '90.	No LU>100. May '89.	No LU>100. May '89.	No fatchup. Mar '90.
Facility	A: 88-in GD: Cf-252	88-in	88-in	.Nd	N N	88-in	88-in BNL	BNL	88-in	88-in	BNL	88-in	d ag		E .9	88.in	88-i.	88-in	88-in	98-in	88-in	88-in	88-in	88-in	88-in
Cross Section Per Bit (sq mic)	1	200	က	1	l	200	200 200 200	230	ı	١	1	!	 	ļ	i i		I	1	1	1	1	I	١	ſ	ſ
Device Cross Section (cm2)***	1	3E-4	l	3E-2	2E-2	I	11	ì	ł	0.1	1	1E-3 (spikes)	2F.5 (1)		3E.5/1)	9E-5(1)	3E-5(1)	1	2E-4(1)	4E-6	3E-6(1)	4E-5(1)	2E-4	2E-5	1E-4(1)
Effective LET** Threshold	ı	30	20	9	9	52	88	52	4	9	ļ	ဗ	64	?	۲ ا	8 8	20	ı	9	55	100	40	20	20	90
Bits E	64	64	į	285X106	160x73	1200 gates	2000 gates 266 F/F	266 F/F	1	1	i	I	ı	1		I	i	ı	I	1	i	ı	I	ļ	1
Mfr.‡	rsi	rsı	rsı	×	×	ACT	ACT	ACT	ALT	CRY	PFS	HAH	NSC	CON	NSC	NSC	NSC	NSC	NSC	1DT	Σ̈́	ž	RCA	¥	Χ̈́
Technology	CMOS	CMOS/epi	CMOS/epi	CMOS	CMOS	CMOS/epi	CMOS/epi CMOS/epi	CMOS/epi	CMOS	CMOS	1	CMOS	FACT/epi	No on	FACT/eni	FACT/epi	FACT/epi	No epi	FACT/epi	CMOS	HCMOS	HCMOS	HCMOS/T	HCMOS/T	HCMOS
Function	Gate Array	Gate Array	Gate Array	FP Gate Array	FP Gate Array	FP Gate Array	FP Gate Array FP Gate Array	FP Gate Array	PAL	A/D Converter	Transceiver	Ор Атр	COGIC	21501	10010	LOGIC	COGIC	LOGIC	rogic	10010	LOGIC	rogic	LOGIC	LOGIC	LOGIC
Test Org* Device	LL7320Q	LRH9320Q	LRH91000	XC3042	XC2064	ACT1010	ACT1020 ACT1020	ACT1020B	EP910JC-40	CS5016	PCT245	C12014-0001	54AC163	54AC163	54AC174	54ACT174	54AC299	54AC299	54ACT373	54FCT374	54HC109	54HC164	54HCT174F	54HCT373J	54HC374
Test Or	A/GD	⋖	⋖	CNES	CNES	⋖ ·	⋖⋥	丐	⋖	⋖	Z	4	∢	⋖	< <	⋖	⋖	⋖	⋖	⋖	⋖	⋖	∢	⋖	4

(1) Aerospace cross sections for AC and HC parts are obtained with Xe or high-angle Kr. Aerospace attempts to find the asymptotic limit at high LET. FACT = Fairchild Advanced CMOS Technology. The NSC FACT process uses 8 micron epi. Those devices with data code 8820 or later are impervious to latchup at LET=120 MeV/(mg/cm²).

1989-1990 (BIPOLAR DEVICES) **TABLE 2 SEU DATA**

Remarks	Feb. '89. The company of the company	reo. 69). Dec. '89. Correction to data. Jan '88.	16. '90. 10 IEEE NS-36, p 2283 (Dec. '89).	May '90. Feb. '89. Nov. '89.	sb. '89. n. '89.	ว latchup. Bradley et al. Dec '90. ลy & Nov. '89.	No latchup. Bradley et al. Dec '90. May & Nov., 1989, Temp=96 deg C.	Same SEU response as part below. May & Nov., 1989. Temp=96 deg C. Same SEU response as part above.
	CIT/88in Fe 88-in Re							.,,
Facility	CIT/4	88-in BNL	8 8	88 88 7- 7- 88 7- 7- 7-	88	58	28	88-in
Cross Section Per Bit (sq mic)	5000 -5000	11	8000	500 2500	2000 2000	11	11	I
Device Cross Section (cm ²)***	3E-3 4E-3	9E-5	5E-3 2E-2	2 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	4-E4 1E-4	4E-6	4E-6	I
Effective LET** Threshold	<< 3.3 3	, 37	£ 8.	8 4 15	4 0	₽	۱۸	ž.
Bits	64 87 tested	IXX	16x4 256x4	16Kx4 2 8 8	æ ~	11	279	279
Mir.†	AMD	AMD FSC	AMD	SGN SGN FSC	ĔĚ	<u>\$</u>	MPS	TRW
Technology	ECL/TTL TTL	Bipolar STTL	STTL STTL LTTL	£££	ALS-TTL S/TTL	湿	Flash Bipolar	hybird Bipolar hybird
Function	4-Bit Slice ROM	PROM PROM	SRAM SRAM SRAM	SRAM D FF Latch	Latch D FF	DAC (12-bit) A/D (10-bit)	A/D/ (8-bit) A/D (8-bit)	A/D (8-bit)
Device	2901C 2910	AM27S49A 93451	54S189 93L422	54F189 54F74 54F373	54ALS373 54S74	AD7543 AD573	MP7683 TDC1048J6A	TDC1048J6C
Test Org•	CNES	∢¬	4 Y	444	רע	g -	g -	7

"J = JPL,A = Aerospace Corp., R = Rockwell Int. or IRT (J. Pickel), SNL = Sandia, NTT = Nippon Tel & Tel Corp., IBM = IBM, H = Hughes (El Segundo, CA), LIN = Lincoln Labs, M.I.T., CNES = Centre National d'Eudes Spatiales (France), GD = General Dynamics (J. Elliott at SEE Symposium, April, '90), ESA = European Space Agency, JH = John Hopkins Applied Physics Lab.
"LET is Linear Energy Transfer = the density of ionization along an ion's path in MeV/(mg/cm²).
"Lolless otherwise noted, the cross section (upsets/fluence per device) is given for 120-360 MeV krypton (or bromine) at normal incidence, having an LET = 37-40
"CV/(mg/cm²).
"To CYCCOLOR (GC-SE) isotope facility; BNL = Brookhaven National Laboratory (Long Island, NY) Tandem Van de Graaff; GANIL = Cyclotron (Caen, France); IPN = Tandem Van de Graaff at Institut de Physique Nucleaire (Orsay, France); 88-in. = Cyclotron UC Berkeley, ESA = European Space Agency site.

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TABLE 3 LATCHUP TEST DATA ONLY 1989-1990

Results (LET** = MeV/(mg/cm²))	Date Code: 9016. LU(LET) = 25; 1E-4 cm ² . 12-micron epi. Chapuis IEEE NS (12/90).	Latchup LET << 37. Cross section (Kr) = 4E-4 cm2,	Cross section ■ 1.3E-5 cm ² @ 85 C; 5E-7 cm ² @ rm T. SEE Symp 4/90.	Latchup	No latchup LET >75. Kinnison '91.	LU(LET) = 13; 4E-3 cm ² , Nov. '90.	LU(LET) = 12; 1E-3cm ² . Sep '89.	One with LU LET< 26; other with LU LET = 53. Aug. '90.	Latchup LET << 37; < 1E-2 cm ² . Date Code 8917, Oct. 1989.	Feb '90. This data from Tandem did not properly locate latchup threshold with ablique angles because of limited beam range. DKN.	Latchup LET 17 ± 5; 4E-3 cm ² . Oct. '89 and Feb. '90.	LU = 14 for each device type.	LU LET = 12; 1E-3 cm ² , Feb. '90,	Latchup LET < 26. Aug. '90.	Latchup LET threshold = 12. LU cross section = 2E-3 cm ² . See Chapuis IEEE NS (12/90).	Latchup > 37; 4E-6 cm ² . Date Code 8921, October '89.	Latchup < 25; 2E-6 cm ² . Feb. '90.	
Facility	Nd	88-in	CI-252	Cf-252	BNL	88-in	88-in	BNL	GANIL	Ā	GANIL & IPN	BNL	88-in	BNL	<u>d</u>	GANIL	Ā	2
Mfr.†	l	AD	IDI	DDC	TRW	Ϋ́	ĭ	Χ̈́	Ϋ́	¥	ZOR	ADI	ADI	MOT	MOT	MTA	MTA	
Technology	CMOS/epi	CMOS	CMOS	Hybrid	CMOS	CMOS/epi	CMOS	CMOS/epi	CMOS/epi	CMOS/epi	CMOS/epi (12-micron)	CMOS	CMOS	CMOS	CMOS/epi (15-micron)	CMOS/epi	CMOS/epi	(10-microri)
Function	ASIC	Multiplier	Multiplier	1553 Bus Controller	FFT Processor	DSP	DSP	DSP	DSP	DSP	Signal Processor	DSP	G DSP	DSP	Fit. Pt. Unit (32-bit)	MicroCont.	MicroCont.	(10-6)
Device	ES 10050	ADSP1016A	IDT7210	DDC61553	TMC2310	320C30	320C25	320C25	320C25	320C25	ZR34161	ADSP2100 & 2100A	ADSP2100ASG	56001	MC68882	MHS80C31	MHS80C31	
Test Org* Device	CNES	7	S S	CD	픙	∢	∢	歬	CNES	CNES	CNES	H	⋖	동	CNES	CNES	CNES	=

J. JPL, A = Aerospace Corp., R = Rockwell Int. or IRT (J. Pickel), SNL = Sandia, NTT = Nippon Tel & Tel Corp., IBM = IBM, H = Hughes (El Segundo, CA), CNES = Centre National d'Etudes Spatiales (France), GD = General Dynamics (J. Elliott at SEE Symposium, April, '90), ESA = European Space Agency, JH = John Hopkins Applied Physics Lab.

"LET is Linear Energy Transfer = the density of ionization along an ion's path in MeV/(mg/cm²).

"Cf = Cf-252 isotope facility; BNL = Brookhaven National Laboratory (Long Island, NY) Tandem Van de Graaff; GANIL = Cyclotron (Caen, France); IPN = Tandem Van de Graaff at Institut de Physique Nucleaire (Orsay, France); 88-in. = Cyclotron UC Berkeley, ESA = European Space Agency site.

Note: Unless otherwise noted, the cross section (upsets/fluence per device) is given for 120-360 MeV krypton (or bromine) at normal incidence, having an LET = 37-40 MeV/(mg/cm²).

TABLE 3 LATCHUP TEST DATA ONLY (CONTINUED) 1989-1990

Test Org.	Device	Function	Technology	Mfr.†	Facility***	Results (LET** = MeV/(mg/cm²))
CNES	P1750A	MicroP	CMOS/epi	PFS	GANIL & IPN	Latchup <11; 7E-3 cm ² . Oct. '89 & Feb. '90. DC 8918 is 1.25 micron technology.
CNES	P1750AE	MicroP	CMOS/epi	PFS	IPN	Feb. '90. Latchup same as above. One-micron technology. Date Code; 8936.
동	P1750AE	MicroP	(9-micron) CMOS/epi	PFS	BNL	Static test gives Latchup threshold = 50. See below. Source: J. D. Kinnison '89,
8	P1750AE	(16-bit) MicroP	(9-micron) CMOS/epi	PFS	ļ	Dynamic test gives LU = 7. See above. E.C. Smith, Apr. '90.
Ŧ	64500/1	MicroP	(9-micron) CMOS/epi	ısı	BNL	1750A CPU. LU threshold = 75.
JH	68020 68020	(16-bit) MicroP MicroP	CWOS	MOT	CI-252 IPN	LU thres < 40. Kinnison '89. Compare with next 4 lines. LU thres = 6. Chapuis '90.
폭	68020	MicroP	CMOS/epi	MO	Cf-252 &	LU thres < 40, 15-micron epi. See above & below.
CNES JH	68020 68020	MicroP MicroP	CMOS/epi CMOS/epi	MOT	PN PN	LU thres >72. 15-micron epi. Compare above and below. Chapuis '90. LU thres >50. 12-micron epi, See above 2 lines.
< =	7201LA 7202BT	FIFO	CMOS (512x9)	55	88-in	LU =13. Cross section = 2E-3. cm ² , Sep. '89.
JHINRL	AMD7202	를 안	CMOS (2Kx9)	A P	BNE	Latchup LET < 26. Jan. '91.
ᆿ.	AMD7204	FIFO	CMOS (4Kx9)	AMD	BNL	Latchup LET < 26. Aug. '90.
⋖ ∃	MP / 682	6-bit AUC	SWOS	MPS	88-in	No LU LET > 100 July '89.
马	CS5016	16-bit ADC	CWOS	8	BNL	Latchup LET << 37.
푯	7134RT	4Kx8 SHAM	CMOS	ΙQ	BNL	Latchup << 37. Kinnison '91.
9	CY7C185	8Kx8 SHAM	CMOS	СУР	CI-252	Latchup cross section = 2E-4 cm² @ 850 C.; 8E-5 cm² at rm Temp.
马	P4C163	8Kx9 SRAM	CMOS	PFS	BNL	Latchup LET = 30. Jan. '91.
A	P4C164L	8Kx8 SRAM	CMOS	PFS	88-in	LU = 8. Cross section = 1E-2 cm ² . Sep. '89.
CARS	MH363162 HM65262	16Kx1 SRAM		¥ ¥ ¥ ¥	NA C	No tatchup (d. LET = 1.2 for 3E3 for 8/Cm², 1.80, 190, 566 CMOS (able.)
CNES	61CD16	16K SRAM	CMOS/epi	Ě	PNI	LU LET(th) <13; cross section at LET=40 is 6E-3 cm². Chapuis '90. Compare to below.
CNES	61CD64S	64K×1 SRAM	CMOS/epi	¥;	GANIL	No latchup up to LET = 116.
SES SES	MB81C81 MT5C2568	256KX1 SHAM 32Kx8 SRAM	CMOS tristate CMOS/epi	3≅	BNL BNL	Feb. '90. No latchup at LET = 114 for 1E4 iodine ions/cm². LU thresh < 40. J Kinnison '89.
A/A	TMS27C256	32Kx8	HVCMOS	ž	88-in	J: No latchup to LET = 120 up to T = 60 deg C. Nov. '89.
		UV-Erasable	epi/guard rings			A. No latchup. Feb. '90.
GD/JH	28C256	EEPROM	CMOS	Š	CI-252	GD: Latchup.
동	28C256	(32Kx8) EEPROM	CMOS/epi	SEQ	N N	JH: Latchup << 37. LU thresh > 120. See above.
∢	28HC64L	(32Kx8) EEPROM	CMOS	ATM	98-in	No LU > 100. Dec. '89.
		(8K×8)				

TABLE 3 LATCHUP TEST DATA ONLY (CONTINUED) 1989-1990

Test Org* Device	Device	Function	Technology	Mfr.†	Facility***	Results (LET** = MeV/(mg/cm²))
CNES	SOR 5053	Coder	CMOS	SOR	Ndl	LU = 9 ± 3. Chapuis '90.
∢	MC10H115FN	Recvr	ECL	MOT	88-in	No LU > 100, Fab. '90.
Ŧ	TSC430	FET Driver	CMOS/epi	TEL	BNL	No LU > 120. JDK '91,
폭	54AC02	Logic	FACT	NSC	BNL	LU thresh > 75. Kinnison '89.
픗	54AC08	Logic	FACT	NSC	BNL	LU thresh > 75. Kinnison '89.
CNES	54AC74	Logic	AdvCMOS/epi	NSC	Ndi	No LU > 72. Feb. '90.
∢	54AC163	Logic	ACMOS	NSC	88-in	LULET = 40; 1E-5 cm ² at high LET. Feb. '90. Date Code 8718. Compare with GANIL data below.
CNES	54AC163	Logic	ACMOS	NSC	GANIL	Latchup LET < 40; > 2E-6 cm ² . Date Code 8718; Oct. '89, Compare above; 2 lines below.
CNES	54AC163	Logic	ACMOS	RCA	GANIL	Latchup LET << 37; >5E-6 cm ² . Date Code 8804: Oct. '99
ᆿ	54ACT163	Logic	FACT	NSC	BNL	LU thresh > 75. Kinnison '89. Re 2 lines above: J.K. says later DC used here is known LU-proof.
푹	54AC174	Logic	FACT	NSC	BNL	LU thresh > 75. J. Kinnison '89.
폭	54ACTQ174	Logic	FACT w. I/O	NSC	BNL	LU thresh > 120. J. Kinnison expects other ACTO's are LU proof
∢	54AC245	Logic	ACMOS/epi	NSC	88-in	LU thresh > 120. Dec '88 & Dec, '89.
∢	54AC245	Logic	No epi	NSC	88-in	LU LET = 60; 1E-6 cm2. Feb. 90.
∢	54ACT253	Logic	ACMOS/epi	NSC	88-in	No latchup. May '90.
∢	54AC299	Logic	No epi	NSC	88·in	LU LET = 60; 2E-5 cm2, Feb. '90.
∢	54ACT374	Logic	No epi	NSC	88-in	LU LET = 50; 5E-6 cm ² . Feb. '90.
톳	P54PCT245	Logic	CMOS	PFS	BNL	LU LET < 40. Kinnison '89.
∢	74HC00D	Logic:	HCMOS	RCA	88-in	No LU > 100. Feb. '90.
∢	54HC03J	Logic:	HCMOS	ΤΙΧ	88-in	No LU > 100. Sept. '89.
∢	74HC04D	Logic	HCMOS	HCA	88-in	No LU > 100. Feb. '90.
∢	54HC11J	Logic	HCMOS	Τİ	88-in	No LU > 100. Sept. '89.
∢	54HC32	Logic	HCMOS	ĭ	88-in	No LU. Mar. '90.
∢	74HC75D	Logic	HCMOS	HCA	88-in	No LU > 100. Feb. '90.
7	54HC139	Logic	HCMOS	ΧI	88-in	No LU > 180. May '89.
7)	54HC154	Logic	HCMOS	ΧĽ	88-in	No LU > 180. May '89.
∢	54HC390J	Logic	HCMOS	ΧI	88-in	No LU > 100, Sept. '89,
∢	54HC595J	Logic	HCMOS	Χİ	88-in	No LU > 100. Sept. '89.
∢	54HCT4059	Logic	HCMOS	BCA	BNL	No LU > 75. Kinnison Jan. '91.

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APPENDIX

MANUFACTURER ABBREVIATIONS

ACT Actel ADI Analog Devices, Incorporated ALS Allied Signal ALT Alpha Industries, Semiconductor Division AMD **Advanced Microdevices Corporation** ATM **CRY** Crystal Semiconductor, Incorporated CYP Cypress Corporation **DDC** DDC ILC Data Device Corporation **FSC** Fairchild Semiconductor Corporation FUJ Fujitsu Ltd. HAR Harris Corporation, Harris Semiconductor Division HIT Hitachi Ltd. Honeywell, Incorporated HON IDT Integrated Device Technologies, Incorporated **INMOS** Corporation INM INT Intel Corporation LSI LSI Logic Corporation **MED** Marconi Electronic Devices Micron Technologies MIC MIT Mitsubishi MOT Motorola Semiconductor Products, Incorporated MPS Micro Power System Matra Harris Semiconductor **MTA** NEC Nippon Electric Corporation **NSC** National Semiconductor Corporation OWI Omni-Wave, Incorporated **PFS** Performance Semiconductor Corporation **RCA** Radio Corporation of America SEI Seiko SEEQ Technology, Incorporated SEQ **SGN** Signetics Corporation SNL Sandia National Laboratories SNY Sony Corporation SOREP SOR TEL Teledyne Crystalonics THO Thomson Military & Space, France TIX Texas Instruments, Incorporated TOS Toshiba TRW TRW, Incorporated XIC Xicor, Incorporated

Xilinx Corporation

Zoran

XIL ZOR

TECHNOLOGY OPERATIONS

The Aerospace Corporation functions as an "architect-engineer" for national security programs, specializing in advanced military space systems. The Corporation's Technology Operations supports the effective and timely development and operation of national security systems through scientific research and the application of advanced technology. Vital to the success of the Corporation is the technical staff's wide-ranging expertise and its ability to stay abreast of new technological developments and program support issues associated with rapidly evolving space systems. Contributing capabilities are provided by these individual Technology Centers:

Electronics Technology Center: Microelectronics, solid-state device physics, VLSI reliability, compound semiconductors, radiation hardening, data storage technologies infrared detector devices and testing; electro-optics, quantum electronics, solid-state lasers, optical propagation and communications; cw and pulsed chemical laser development, optical resonators, beam control, atmospheric propagation, and laser effects and countermeasures; atomic frequency standards, applied laser spectroscopy, laser chemistry, laser optoelectronics, phase conjugation and coherent imaging, solar cell physics, battery electrochemistry, battery testing and evaluation.

Mechanics and Materials Technology Center: Evaluation and characterization of new materials: metals, alloys, ceramics, polymers and their composites, and new forms of carbon; development and analysis of thin films and deposition techniques; nondestructive evaluation, component failure analysis and reliability; fracture mechanics and stress corrosion; development and evaluation of hardened components; analysis and evaluation of materials at cryogenic and elevated temperatures; launch vehicle and reentry fluid mechanics, heat transfer and flight dynamics; chemical and electric propulsion; spacecraft structural mechanics, spacecraft survivability and vulnerability assessment; contamination, thermal and structural control; high temperature thermomechanics, gas kinetics and radiation; lubrication and surface phenomena.

Space and Environment Technology Center: Magnetospheric, auroral and cosmic ray physics, wave-particle interactions, magnetospheric plasma waves; atmospheric and ionospheric physics, density and composition of the upper atmosphere, remote sensing using atmospheric radiation; solar physics, infrared astronomy, infrared signature analysis; effects of solar activity, magnetic storms and nuclear explosions on the earth's atmosphere, ionosphere and magnetosphere; effects of electromagnetic and particulate radiations on space systems; space instrumentation; propellant chemistry, chemical dynamics, environmental chemistry, trace detection; atmospheric chemical reactions, atmospheric optics, light scattering, state-specific chemical reactions and radiative signatures of missile plumes, and sensor out-of-field-of-view rejection.